

East 8 USPB, USPT, WPID, JPO

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	120362	nonionic or "non ionic"	US-PGPUB; USPAT	OR	OFF	2005/09/20 13:31
L2	236082	surfactant or "wetting agent"	US-PGPUB; USPAT	OR	ON	2005/09/20 13:32
L3	551166	cmp or \$polish\$ or chemimech\$ or planariz\$ or lap\$ or grind\$ or abrad\$	US-PGPUB; USPAT	OR	ON	2005/09/20 13:32
L4	334738	poly or polysi or polysilicon or "polyc\$ si" or "polyc\$ silicon"	US-PGPUB; USPAT	OR	ON	2005/09/20 12:57
L5	0	"ethylene oxide propylene oxide"	US-PGPUB; USPAT	OR	ON	2005/09/20 12:52
L6	98272	"ethylene oxide" or ethyleneoxide	US-PGPUB; USPAT	OR	ON	2005/09/20 12:57
L7	55433	"propylene oxide" or propyleneoxide	US-PGPUB; USPAT	OR	ON	2005/09/20 12:58
L8	43927	6 with 7	US-PGPUB; USPAT	OR	ON	2005/09/20 12:53
L9	17909	8 with (polymer or copolymer)	US-PGPUB; USPAT	OR	ON	2005/09/20 12:58
L10	71111	1 with 2	US-PGPUB; USPAT	OR	ON	2005/09/20 12:53
L11	1427	3 same 10	US-PGPUB; USPAT	OR	ON	2005/09/20 12:53
L12	1427	10 same 11	US-PGPUB; USPAT	OR	ON	2005/09/20 12:54
L13	14	11 same 9	US-PGPUB; USPAT	OR	ON	2005/09/20 12:54
L14	1	4 same 13	US-PGPUB; USPAT	OR	ON	2005/09/20 12:55
L15	13	13 not 14	US-PGPUB; USPAT	OR	ON	2005/09/20 12:55
L16	46412	nonionic or "non ionic"	JPO; DERWENT	OR	OFF	2005/09/20 12:57
L17	131797	surfactant or "wetting agent"	JPO; DERWENT	OR	ON	2005/09/20 13:48
L18	333885	cmp or \$polish\$ or chemimech\$ or planariz\$ or lap\$ or grind\$ or abrad\$	JPO; DERWENT	OR	ON	2005/09/20 13:03
L19	274337	poly or polysi or polysilicon or "polyc\$ si" or "polyc\$ silicon"	JPO; DERWENT	OR	ON	2005/09/20 13:32
L20	25257	"ethylene oxide" or ethyleneoxide	JPO; DERWENT	OR	ON	2005/09/20 13:33
L21	13414	"propylene oxide" or propyleneoxide	JPO; DERWENT	OR	ON	2005/09/20 13:33

L22	1357917	polymer or copolymer	JPO; DERWENT	OR	ON	2005/09/20 13:34
L23	31339	16 with 17	JPO; DERWENT	OR	ON	2005/09/20 12:58
L24	741	23 and 18	JPO; DERWENT	OR	ON	2005/09/20 12:58
L25	1363544	20 with 21 with 22	JPO; DERWENT	OR	ON	2005/09/20 13:48
L26	241	24 and 25	JPO; DERWENT	OR	ON	2005/09/20 12:59
L27	22	19 and 26	JPO; DERWENT	OR	ON	2005/09/20 13:00
L28	0	27 not 26	JPO; DERWENT	OR	ON	2005/09/20 13:00
L29	219	26 not 27	JPO; DERWENT	OR	ON	2005/09/20 13:00
L30	78	29 and (cmp or \$polish\$ or chemimech\$ or planariz\$ or lap\$ or grind\$ or abrad\$).ti.	JPO; DERWENT	OR	ON	2005/09/20 13:03
L31	78	30 not 27	JPO; DERWENT	OR	ON	2005/09/20 13:04
L32	0	30 not 29	JPO; DERWENT	OR	ON	2005/09/20 13:04
L33	141	29 not 30	JPO; DERWENT	OR	ON	2005/09/20 13:29
L34	5	"5256402"	JPO; DERWENT	OR	ON	2005/09/20 13:30
L35	1	33 and 34	JPO; DERWENT	OR	ON	2005/09/20 13:30
L36	22978	(nonionic or "non ionic").clm.	US-PGPUB; USPAT	OR	OFF	2005/09/20 13:31
L37	48783	(surfactant or "wetting agent").clm.	US-PGPUB; USPAT	OR	ON	2005/09/20 13:32
L38	81010	(cmp or \$polish\$ or chemimech\$ or planariz\$ or lap\$ or grind\$ or abrad\$).clm.	US-PGPUB; USPAT	OR	ON	2005/09/20 13:32
L39	0	(poly or polysi or polysilicon or "polyc\$ si" or "polyc\$ silicon").clm.	JPO; DERWENT	OR	ON	2005/09/20 13:34
L40	0	("ethylene oxide" or ethyleneoxide).clm.	JPO; DERWENT	OR	ON	2005/09/20 13:33
L41	8083	("propylene oxide" or propyleneoxide).clm.	US-PGPUB; USPAT	OR	ON	2005/09/20 13:33
L42	14643	("ethylene oxide" or ethyleneoxide).clm.	US-PGPUB; USPAT	OR	ON	2005/09/20 13:33
L43	70836	(poly or polysi or polysilicon or "polyc\$ si" or "polyc\$ silicon").clm.	US-PGPUB; USPAT	OR	ON	2005/09/20 13:34

L44	241197	(polymer or copolymer).clm.	US-PGPUB; USPAT	OR	ON	2005/09/20 13:34
L45	14143	36 with 37	US-PGPUB; USPAT	OR	ON	2005/09/20 13:34
L46	405	45 and 38	US-PGPUB; USPAT	OR	ON	2005/09/20 13:35
L47	2642	41 with 42 with 44	US-PGPUB; USPAT	OR	ON	2005/09/20 13:35
L48	12	46 and 47	US-PGPUB; USPAT	OR	ON	2005/09/20 13:35
L49	4	43 and 48	US-PGPUB; USPAT	OR	ON	2005/09/20 13:36
L50	8	48 not 49	US-PGPUB; USPAT	OR	ON	2005/09/20 13:39
L51	58	2 same 3 same 8	US-PGPUB; USPAT	OR	ON	2005/09/20 13:39
L52	22	2 same 3 same 9	US-PGPUB; USPAT	OR	ON	2005/09/20 13:39
L53	11	(51 or 52) same 4	US-PGPUB; USPAT	OR	ON	2005/09/20 13:40
L54	11	53 not 35	US-PGPUB; USPAT	OR	ON	2005/09/20 13:41
L55	8	52 not 13	US-PGPUB; USPAT	OR	ON	2005/09/20 13:43
L56	47	51 not (35 or 54)	US-PGPUB; USPAT	OR	ON	2005/09/20 13:44
L57	8152	20 with 21	JPO; DERWENT	OR	ON	2005/09/20 13:48
L58	38	17 and 18 and 57	JPO; DERWENT	OR	ON	2005/09/20 13:48

STNG Caplus

(FILE 'HOME' ENTERED AT 15:17:38 ON 20 SEP 2005)

FILE 'REGISTRY' ENTERED AT 15:17:45 ON 20 SEP 2005

L1 1909 S ETHYLENE/CNS AND OXIDE/CNS AND PROPYLENE/CNS
L2 1675 S L1 AND COPOLYMER/CNS
L3 0 S L1 AND (TRI-BLOCK POLYMER)/CNS
L4 0 S L1 AND (TRIBLOCK POLYMER)/CNS
L5 5 S L1 AND TRI/CNS AND BLOCK/CNS AND POLYMER/CNS
L6 15 S L2 AND ALCOHOL/CNS

FILE 'CAPLUS' ENTERED AT 15:20:00 ON 20 SEP 2005

FILE 'CAPLUS' ENTERED AT 15:20:30 ON 20 SEP 2005

L7 216740 S CMP OR ?POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? OR GRIND?
L8 0 S L5 AND L7
L9 7 S L6 AND L7
L10 16054 S (ETHYLENE(3A)OXIDE) (10A) (PROPYLENE(3A)OXIDE)
L11 12839 S L10 AND (POLYMER OR COPOLYMER OR BLOCK OR TRIBLOCK OR ALCOHOL
L12 200 S L7 AND L11
L13 6 S L9 AND L12
L14 7 S L9 OR L13
L15 5 S L14 NOT FLOOR
L16 194 S L12 NOT L14
L17 183 S L16 NOT FLOOR
L18 386 S L2 AND L7
L19 366 S L18 NOT (L14 OR FLOOR)
L20 158 S L10 AND L19
L21 151 S L12 AND L20
L22 43 S L21 AND (ABRAS? OR SILICA OR CERIA OR TITANIA OR ZIRCONIA OR

FILE 'REGISTRY' ENTERED AT 15:28:10 ON 20 SEP 2005

L23 4 S SILICA/CN OR CERIA/CN OR TITANIA/CN OR ALUMINA/CN

FILE 'CAPLUS' ENTERED AT 15:28:44 ON 20 SEP 2005

L24 33 S L21 AND L23
L25 45 S L22 OR L24
L26 106 S L21 NOT L25
L27 19 S L26 AND (CMP OR ?POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? O

FILE 'REGISTRY' ENTERED AT 15:31:20 ON 20 SEP 2005

FILE 'CAPLUS' ENTERED AT 15:31:21 ON 20 SEP 2005

L28 87 S L26 NOT L27